

AMENDMENTS TO THE CLAIMS

This listing of claims replaces all prior versions, and listings, of claims in the application.

Claims 1-13 (Cancelled).

14. (Currently Amended) A substrate treatment apparatus comprising:
a substrate heating device for maintaining a substrate at a temperature higher than room temperature;
a wetting device for producing a wet ozone-containing gas by wetting an ozone-containing gas with a treatment solution;
a supply device for supplying the wet ozone-containing gas from the wetting device to a work object on a surface of the substrate, ~~said supply device comprising a gas disperser including a plurality of apertures aligned in a plurality of rows in a width direction of the work object, the apertures in adjacent rows not being aligned with each other in a direction perpendicular to the rows, and at least one of said gas disperser and the substrate being movable in a direction perpendicular to the rows;~~
a gas conduit connecting said wetting device to said supply device; and
~~a wet ozone-containing gas heating device for heating the wet ozone-containing gas to a temperature at least equal to the temperature of the substrate, the wet ozone-containing gas heating device comprising a header containing a heater and located at said gas conduit, proximate said supply device.~~

Claim 15 (Canceled).

16. (Currently Amended) The substrate treatment assembly according to Claim ~~14~~ ~~19~~, wherein spacing between adjacent rows of apertures in said gas disperser is at least 5 mm.

17. (Withdrawn) A substrate treatment apparatus for supplying an ozone-containing gas and a treatment solution to a work object on a surface of a substrate, the assembly including a treatment agent supply plate facing the work object and through which the treatment solution is supplied, wherein a surface of the work object is spaced from said treatment agent supply plate by a distance in a range between 0.1 mm and 1.0 mm.

18. (New) The substrate treatment assembly according to Claim 14 wherein said wet ozone-containing gas heating device includes a conduit heater in thermal contact with said gas conduit.

19. (New) The substrate treatment assembly according to Claim 14 wherein, said supply device comprises a gas disperser including a plurality of apertures aligned in a plurality of rows in a width direction of the work object, the apertures in adjacent rows not being aligned with each other in a direction perpendicular to the rows, and at least one of said gas disperser and the substrate being movable in a direction perpendicular to the rows.

20. (New) A substrate treatment apparatus comprising:
a wetting device for producing a wet ozone-containing gas by wetting an ozone-containing gas with a treatment solution;
a supply device for supplying the wet ozone-containing gas from the wetting device to a work object on a surface of the substrate;
a gas conduit connecting said wetting device to said supply device;
a transparent header located at said gas conduit, proximate said supply device; and
an infrared heating device proximate said header, said header being interposed between said infrared heating device and said supply device, said infrared heater heating the wet ozone-containing gas and the substrate.

21. (New) The substrate treatment assembly according to Claim 20 wherein said wet ozone-containing gas heating device includes a conduit heater in thermal contact with said gas conduit.

22. (New) The substrate treatment assembly according to Claim 20 wherein, said supply device comprises a gas disperser including a plurality of apertures aligned in a plurality of rows in a width direction of the work object, the apertures in adjacent rows not being aligned with each other in a direction perpendicular to the rows, and at least one of said gas disperser and the substrate being movable in a direction perpendicular to the rows.

23. (New) The substrate treatment assembly according to Claim 22, wherein spacing between adjacent rows of apertures in said gas disperser is at least 5 mm.